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PRE-APPEAL BRIEF REQUEST FOR REV			224 (SS-19575-US)
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Patents, P.O. Box 1450, Alexandria, VA 22313-1450" [37 CFR 1.8(a)] on	First Named Inventor Jin Kook Jung		
Signature			I=
Typed or printed Frank Chau	Art Unit		Examiner
name	2826		Benjamin P. Sandv
This request is being filed with a notice of appeal.			
This request is being filed with a notice of appeal. The review is requested for the reason(s) stated on the attance Note: No more than five (5) pages may be provided.		s).	
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The review is requested for the reason(s) stated on the attantomer. I am the applicant/inventor. assignee of record of the entire interest. See 37 CFR 3.71. Statement under 37 CFR 3.73(b) is enclosed.		F Typec 51	rank Chau
The review is requested for the reason(s) stated on the attance. Note: No more than five (5) pages may be provided. I am the applicant/inventor. assignee of record of the entire interest. See 37 CFR 3.71. Statement under 37 CFR 3.73(b) is enclosed. (Form PTO/SB/96) x attorney or agent of record.		Typec 51	rank Chau dor printed name 16-692-8888

This collection of information is required by 35 U.S.C. 132. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.11, 1.14 and 41.6. This collection is estimated to take 12 minutes to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Accomments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Mail Stop AF, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

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8021-224 (SS-19575-US)



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANTS:

Jung et al.

EXAMINER: Sandvik, Benjamin P

SERIAL NO.:

10/822,384

GROUP ART UNIT: 2826

FILED:

April 12, 2004

FOR:

SEMICONDUCTOR DEVICE AND METHOD OF LOCATING A

PREDETERMINED POINT ON THE SEMICONDUCTOR

DEVICE

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

PRE-APPEAL BRIEF REQUEST FOR REVIEW

Sir:

This paper is being filed with a Notice of Appeal Form (PTO/SB/31) and a Pre-Appeal Brief Request For Review Form (PTO/SB/33).

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States	
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P.O. Box 1450, Alexandria, VA 22313-1450 on December 11, 2007.	

Dated:

Frank Char

REMARKS

Please consider the following reasons for this Pre-Appeal Brief Request For Review.

Claims 1-4, 23 and 24 are pending and stand rejected in the above-referenced application.

Claims 1-4, 23 and 24 stand rejected under 35 U.S.C. § 102(e) as being anticipated by Wang et al (U.S. Pub. 2002/0175419). However, there are clear errors in Examiner's rejections based on Wang.

Claim 1 recites, *inter alia*, a number of dummy patterns substantially greater than a number of marking patterns. For example, in the present disclosure, the number of dummy patterns (110) is substantially greater than the number of marking patterns (115). See e.g., Fig. 4 of the present disclosure.

In the October 11, 2007 Final Office Action, the Examiner states that Wang teaches dummy patterns (700) and marking patterns (1200) wherein a number of the dummy patterns (700) is substantially greater than a number of the marking patterns (1200). See October 11, 2007 Final Office Action, Page 2. In stark contrast to the Examiner's assertion, elements (1200) are not marking patterns, but vias. The vias form plugs when filled with metal layer. See e.g., paragraph [0075] of Wang. As such, the vias (1200) cannot be used as marking patterns used for counting the dummy patterns.

Furthermore, even assuming, *arguendo*, that elements (1200) can be marking patterns, Wang does not disclose that a number of the dummy patterns (700) is substantially greater than a number of the marking patterns because if the vias (1200)

in Fig. 12B can be marking patterns, other vias (600) in Fig. 12B can also be marking patterns. Then, in contrast to the Examiner's assertion, in Wang, a number of marking patterns (1200) is greater than a number of patterns (700). See e.g., Fig. 12B of Wang.

Claim 23 recites, *inter alia*, marking patterns surrounding at least a group of dummy patterns. For example, in the present disclosure, marking patterns (215) surround at least a group of dummy patterns (210). <u>See e.g.</u>, Fig. 5 of the present disclosure.

In the October 11, 2007 Final Office Action, the Examiner states that Wang teaches dummy patterns (1200) and marking patterns (700). See October 11, 2007 Final Office Action, Page 3. In stark contrast to the Examiner's assertion, elements (1200) are not dummy patterns for a CMP method formed in a uniform pattern over the semiconductor substrate. As discussed above, the elements (1200) are vias. Furthermore, even assuming, *arguendo*, that the elements (1200) can be dummy patterns, the patterns (700) do not surround a group of the dummy patterns. In contrast, only a single via (1200) is surrounded by the patterns (700). See e.g., Fig. 12B of Wang.

Claim 24 recites, *inter alia*, marking patterns and the predetermined plural numbers of the dummy patterns grouped by the marking patterns form a unit, which is repeated. As stated above, elements (1200) are vias, not marking patterns.

Therefore, there are clear errors in Examiner's rejections based on Wang.

An early and favorable reconsideration is earnestly solicited.

Respectfully submitted,

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